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On April 11, 2002

TOWNSEND and TOWNSEND and CREW LLP

By: Bonnie Reckles

PATENT  
Attorney Docket No.: 00939B-078800US  
Client Ref. No.: 2000-OPH-2014/EYL

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Jae Chang JUNG et al.

Application No.: 09/728,535

Filed: December 1, 2000

For: OVER-COATING COMPOSITION  
FOR PHOTORESIST, AND  
PROCESSES FOR FORMING  
PHOTORESIST PATTERNS USING  
THE SAME

Examiner: Cynthia Hamilton

Art Unit: 1752

RESPONSE TO RESTRICTION  
REQUIREMENT

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RESPONSE TO RESTRICTION REQUIREMENT

This responds to the Office Action having a mailing date of March 19, 2002.

REMARKS

Claims 1-20 are pending in this application. The Examiner has restricted the pending claims into the following groups:

- I. Claims 1-13, drawn to an overcoating composition, classified in class 430, subclass 273.1.
- II. Claims 14-19, drawn to a process of imaging, classified in class 430, subclass 296.